



<b>Form 1449 (Modified)</b>  <b>Information Disclosure Statement By Applicant</b>  (Use Several Sheets if Necessary)	Atty Docket No.	Application No.:
	NOVLP088/NVLS-2882	10/825,888
	Applicant:	
	Bandyopadhyay et al.	
	Filing Date	Group
	April 16, 2004	2812

#### U.S. Patent Documents

Examiner Initial	No.	Publication/ Patent No.	Date	Patentec	Class	Sub- class	Filing Date
BKS	A1	6,329,017	12/11/01	Liu et al.			10/04/99
	A2	6,383,466	5/7/02	Domansky et al.			12/28/98
	A3	6,365,266	4/2/02	MacDougall et al.			03/03/00
	A4	5,504,042	4/2/96	Cho et al.			06/23/94
	A5	5,858,457	1/12/96	Brinker et al.			09/25/97
	A6	6,270,846	8/7/01	Brinker et al.			03/02/00
	A7	6,387,453	5/14/02	Brinker et al.			03/02/00
	A8	6,420,441	<del>10/10/99</del>	Allen et al. 7/2002			12/10/99
	A9	6,271,273	<del>10/10/00</del>	You et al. 8/2001			10/10/00
	A10	20040096672	05/20/04	Lukas et al.			11/14/02
	A11	6,444,715	09/03/02	Mukherjee, et al.			06/06/00

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5/21/07

#### Other Documents

Examiner Initial	No.	Author, Title, Date, Place (e.g. Journal) of Publication
BKS	A12	Humayun et al., "Method For Forming Porous Films By Porogen Removal Combined With In Situ Surface Modification", U.S. Application No. 10/404,693, filed March 31, 2003
	A13	Cho et al., "Method And Apparatus For UV Exposure Of Low Dielectric Constant Materials For Porogen Removal And Improved Mechanical Properties", U.S. Patent Application No. 10/800,377, filed March 11, 2004
	A14	Wu et al., "Methods Of Porogen Removal For Porous Low Dielectric Constant Films Using Plasma Treatments", U.S. Patent Application No. 10/807,680, filed March 23, 2004
	A15	Tipton et al., "Method Of Porogen Removal From Porous Low-K Films Using Uv Radiation", U.S. Patent Application No. 10/672,311, filed September 26, 2003
Examiner	Date Considered	
	6/24/06	

Examiner: Initial citation considered. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.